

CORRECTION

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Cite this: *Inorg. Chem. Front.*, 2024, **11**, 5359Correction: Mechanical force-driven multi-state memory in $\text{WO}_{3-\delta}$ thin filmsMingdi Yang,^a Zonglin Lv,^a Shan Li,^a Jiaqi Li,^a Jinpeng Cao,^a Junjie Chen,^a
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Correction for 'Mechanical force-driven multi-state memory in $\text{WO}_{3-\delta}$ thin films' by Mingdi Yang *et al.*, *Inorg. Chem. Front.*, 2024, **11**, 3919–3926, <https://doi.org/10.1039/D4QI00789A>.

The authors regret that the data in Fig. 3(i) were incorrect in the original article. The corrected figure is included below. Fig. S4 also contained incorrect data and this figure has been corrected in an updated supplementary information file.

In the corrected figure, Fig. 3(i) shows the Schottky fitting results of HRS induced by mechanical force, and the slope values are 8.56 (previously 9.49) in the negative voltage area and 13.16 (previously 10.65) in the positive voltage area. The corrected Fig. S4 shows the Schottky fitting results of HRS induced by voltage, and the slope values are 14.83 (previously 8.53) in the negative voltage area and 15.08 (previously 9.97) in the positive voltage area.

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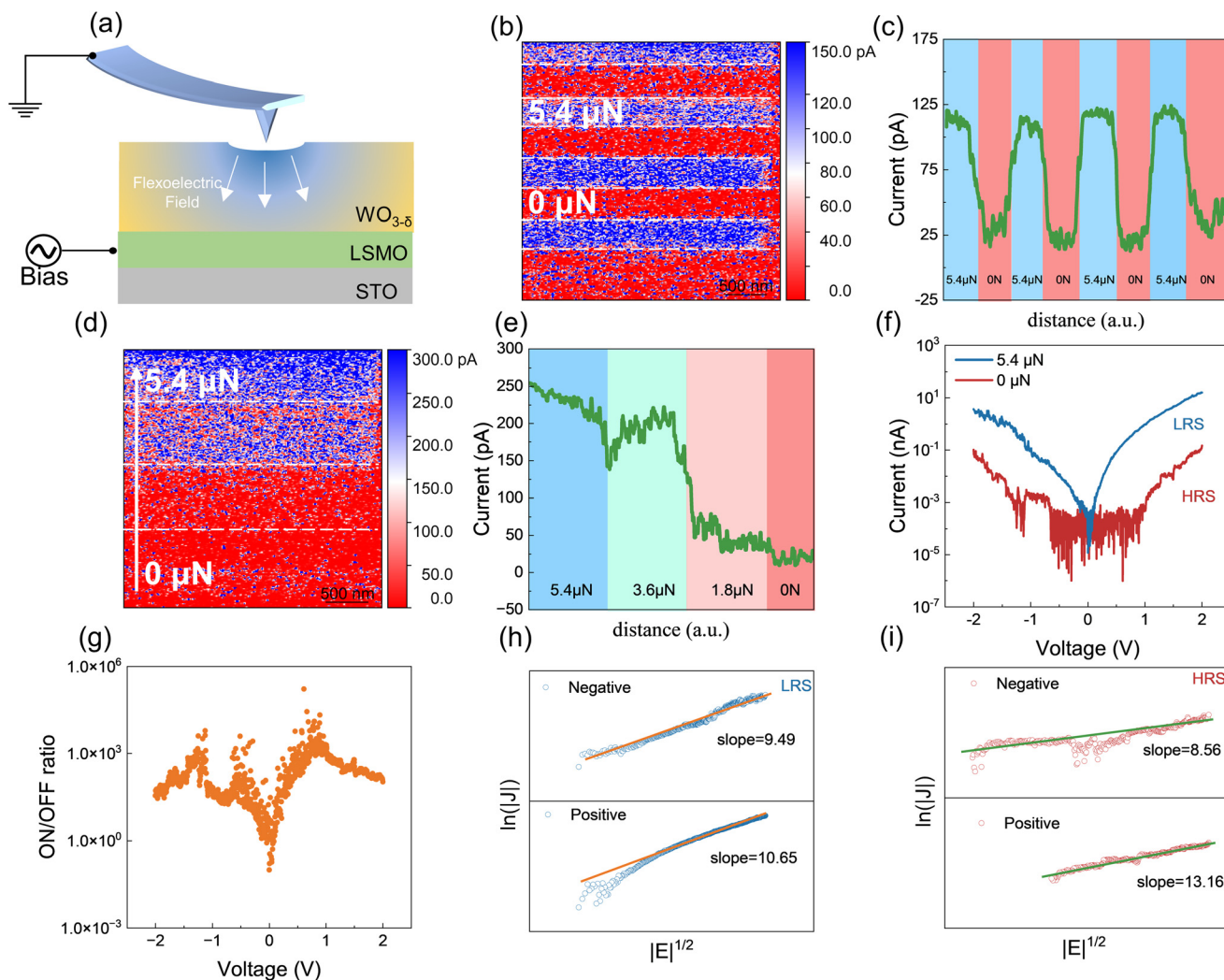


Fig. 3 The resistive switching of the $\text{WO}_{3-\delta}$ thin film with respect to mechanical force. (a) Schematic diagram of applying mechanical force by CAFM. (b) and (d) CAFM plots after different mechanical forces applied. (c) and (e) Corresponding current statistics charts. (f) I - V curves after different mechanical forces applied. (g) ON/OFF ratios. (h) and (i) I - V curve fittings for Schottky emission.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

